



Pulsed Laser Deposition (PLD) Laboratory:

Coherent COMPex Pro 102, $\lambda=248$ nm, KrF Excimer Laser with tunable energy (400 mJ) per pulse, maximum repetition rate 20 Hz. Deposition chamber with programmable multi-target holder for multi-stage deposition of thickness variation from a few nanometers to hundreds of nanometer. Deposition temperature variation from room temperature to 750°C. Deposition in vacuum or partial O₂ pressure. This technique can help synthesize even the most difficult complex oxides in single-phase crystalline thin film form.